



Atty. Docket No. 8043-1004

PATENTS

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Box AF

Katsuhisa YUDA

Confirmation No. 6697

Serial No. 09/729,193

GROUP 1763

Filed December 5, 2000

Examiner L. Alejandro Mulero

PLASMA CVD APPARATUS COMPRISING
A PLASMA CONFINING ELECTRODE

AMENDMENT AFTER FINAL REJECTION

Commissioner for Patents

Washington, D.C. 20231

Sir:

Responsive to the Official Action of October 29, 2002,
please amend the above-identified application as follows:

IN THE CLAIMS:

Amend claim 1 as follows:

C1

--1. (twice amended) A plasma CVD apparatus comprising
a substrate processing zone with a deposition substrate area
disposed therein, a plasma generating zone for generating plasma
of a first gas, and a plasma confining electrode for separating
the substrate processing zone and the plasma generating zone and
confining the first gas and having holes for passing the first
gas containing neutral radicals from the first gas plasma such
that the first gas is uniformly supplied to the substrate
processing zone, wherein

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